

ISO 14606:2000-10 (E)

Surface chemical analysis - Sputter depth profiling - Optimization using layered systems as reference materials

Contents		Page
1	Scope	1
2	Terms and definitions	1
3	Symbols and abbreviated terms	2
4	Setting parameters for sputter depth profiling	2
5	Depth resolution at an ideally sharp interface in sputter depth profiles	4
6	Procedures for optimization of parameter settings	6
Annexes A Factors influencing the depth resolution		9
A.1	General	9
A.2	Sputtering parameters	9
A.3	Measurement parameters	9
A.4	Experimental considerations	10
B	Typical single-layered systems as reference materials	11
C	Typical multilayered systems used as reference materials	12
D	Uses of multilayered systems	13
D.1	Relative sputtering rate	13
D.2	Dependence of depth resolution	13
D.3	Drift of ion beam current	13
Bibliography		14